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Journal Information

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Classification History

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2026		✓	✓	
2025		✓	✓	
2024		✓	✓	
2023		✓	✓	
2021/2022		✓	✓	
2020		✓	✓	
2019		✓	✓	
2018		✓		

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Recent Articles

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2026-7-31 Vol. 39 Issue 2 Pages 137-144
Authors: Katsuaki Takashima, Hidekazu Konishi, Yuichirou Tanaka et al.
DOI: 10.2494/photopolymer.39.137

Dissolution Kinetics of Poly(4-hydroxystyrene) Film in Alcohol/water Mixture -Development Simulation of Polymer Films Using Intrinsic Viscosity and Huggins Coefficient-
2026-7-31 Vol. 39 Issue 2 Pages 91-98
Authors: Mikiko Kozawa, Yuko Tsutsui Ito, Kayoko Cho et al.
DOI: 10.2494/photopolymer.39.91

Improvement of Non-PFAS Biomass EUV Resist by Optimization of Chemical Structures
2026-7-31 Vol. 39 Issue 3 Pages 159-164
Authors: Sotaro Fukumoto, Yuki Yoshikura, Yuki Yanagisawa et al.
DOI: 10.2494/photopolymer.39.159

Moth-eye nanostructured surface with patterned superhydrophilic regions on a superhydrophobic background
2026-7-31 Vol. 39 Issue 3 Pages 189-195
Authors: Takuto Wakasa, Jun Taniguchi
DOI: 10.2494/photopolymer.39.189

Influence of Underlayer Material Parameters on Pattern Collapse in EUV Patterning
2026-7-31 Vol. 39 Issue 2 Pages 85-89
Authors: Hyeon Woo Shin, Stanfield Youngwon Lee, Jiyoung Hwang et al.
DOI: 10.2494/photopolymer.39.85

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2026-7-31 Vol. 39 Issue 4 Pages 263-269
Authors: Atsushi Sekiguchi, Tomoki Iwaoka, Hiroshi Kobayashi et al.
DOI: 10.2494/photopolymer.39.263

Patterning Materials for Lithography: Moving in New Directions
2026-7-31 Vol. 39 Issue 1 Pages 29-35
Authors: Harry J. Levinson
DOI: 10.2494/photopolymer.39.29

Development of Reactive Molecular Dynamics for Cross-linked Polymer Networks
2026-7-31 Vol. 39 Issue 4 Pages 277-282
Authors: Minoru Hoshino, Masaru Yamasaki, Yohei Okoda et al.
DOI: 10.2494/photopolymer.39.277

Engineering the Future of EUV Lithography: A Collaborative Journey in Metal-Oxide Resist Innovation
2026-7-31 Vol. 39 Issue 2 Pages 67-84
Authors: Danilo De Simone
DOI: 10.2494/photopolymer.39.67

Observation of Crystal-to-Liquid and Liquid-to-Solid Phase Transitions of Azobenzene Crystals in Response to Light Wavelengths
2026-7-31 Vol. 39 Issue 4 Pages 271-275
Authors: Mina Han
DOI: 10.2494/photopolymer.39.271